



NOTES

1. MATERIAL: UVFS
2. CLEAR APERTURE: $>90\%CA$
3. SURFACE QUALITY(S1, S2): 40/20(S/D)
4. WAVEFRONT ERROR(RMS): $\lambda/4@633\text{ nm}$ (SUBSTRATE)
5. PARALLELISM(S1, S2): $<3\text{ arcmin}$
6. ARROW POINTS TO THE FILTERING COATING
7. COATING:
 - FILTERING(S1): $T_{\text{avg}}>90\%$, $T_{\text{abs}}>85\%@1260-1700\text{ nm}$, 45° AOI
 $R_{\text{avg}}>95\%$, $R_{\text{abs}}>90\%@750-1100\text{ nm}$, 45° AOI
 - AR COATING(S2): $R_{\text{abs}}<2\%@1260-1700\text{ nm}$, 45° AOI

DRAWING PROJECTION			LBTEK			
	NAME	DATE	DM10-1180LP			
DRAWN	LZHOU	JUL./30th/24	LONGWAVE DICHOIC MIRROR $\varnothing 25.4\text{ mm} \times 3.2\text{ mm}$, 1180 nm			
APPROVAL	WCHENG	JUL./30th/24	MATERIAL	WEIGHT	SCALE	REV
FOR INFORMATION ONLY NOT FOR MANUFACTURING PURPOSES			UVFS	3.6 g	2:1	B